

IBE/RIBE Series

Uni-body Design Concept

Foot-print outstanding (ref 1.0m*0.8m)

Maintenance and Sample-handling Friendly

Sample holder and ion source design for easy-to use

Flexible Ion Source Design

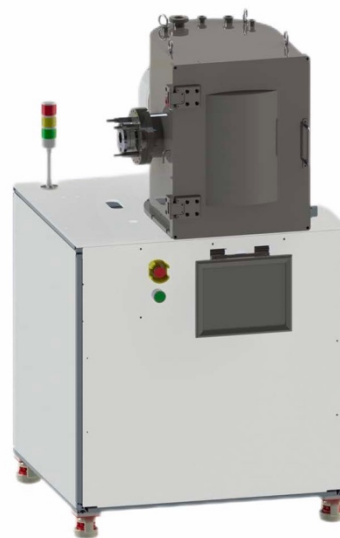
Different kinds of ion source easy-to swap design, depending on customer requirements

Cost or Performance Orientation

Ion Source, Pump, Values etc. depending on requirements

Sample Handling Options

Open-Load or Load-Lock



| Specification | Kaufman ion source | RF ion Source |
|---------------------|---|--------------------------------|
| Wafer Size Range | up to 6 inch | up to 12 inch |
| Gas System | 1 line(standard) or customized | 3 line(standard) or customized |
| Wafer Stage Motion | Tilt from 0° to 90°, Rotation from 1-10 rpm/min | |
| Wafer Stage Cooling | From 5 to 20°C, Water cooling; He backside cooling optional | |
| Vacuum | TMP&Mechanical Pump | |
| Base Vacuum | Better than 7E-7Torr | |
| Non-Uniformity | Less than ±5%(Edge Exclusion) | |